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MAY 06 2008

Application No.:10/728,135

Docket No.:JCLA12578-R

REMARKSPresent Status of the Application

The Office Action dated February 11, 2008 indicated that claims 1, 3-4, 6-8 and 10 would be allowable if written or amended to overcome the rejections under 35 U.S.C. 112, 2nd paragraph. Claims 1, 3-4, 6-8 and 10 were rejected under 35 U.S.C. 112, 2nd paragraph, as being indefinite.

Applicant has amended claims 1 and 7 to more explicitly describe the claimed invention for clarification purposes. It is believed that no new matters have been added by amending the claims and specification. Entry of these amendments is gratefully requested. After considering the following remarks, reconsideration and withdrawal of these rejections are respectfully requested.

Discussions of the 112 rejections

Claims 1, 3-4, 6-8 and 10 were rejected under 35 U.S.C. 112, 2nd paragraph, as being indefinite.

Claims 1 and 7 have been amended respectively to more explicitly describe the claimed invention for clarification purposes and to provide proper antecedent basis. Entry of these amendments is earnestly requested.

As amended, claim 1 clearly recites removing "*the exposed portion of the photoresist layer and the protective layer on the exposed portion of the photoresist layer*". Similarly, the amended claim 7 clearly recites removing "*the exposed portion of the photoresist layer, the acid*

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supplying layer on the exposed portion of the photoresist layer, the protective layer on the exposed portion of the photoresist layer, and the sidewall portion of the unexposed portion of the photoresist layer” for clarification purposes.

Moreover, in order to provide proper antecedent basis, claim 1 or 7 has been respectively amended by incorporating descriptions “*wherein the exposed portion of the photoresist layer and the protective layer on the exposed portion of the photoresist layer are soluble*” or “*wherein the exposed portion of the photoresist layer, the acid supplying layer on the exposed portion of the photoresist layer, the protective layer on the exposed portion of the photoresist layer, and the sidewall portion of the unexposed portion of the photoresist layer are soluble*”.

Accordingly, reconsideration and withdrawal of these 112 rejections are earnestly requested.

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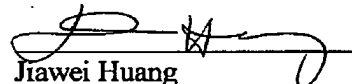
CONCLUSION

In view of the foregoing, it is believed that all pending claims are in proper condition for allowance. If the Examiner believes that a conference would be of value in expediting the prosecution of this application, he is cordially invited to telephone the undersigned counsel to arrange for such a conference.

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Respectfully submitted,
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